

-> d his

(FILE 'HOME' ENTERED AT 09:42:26 ON 21 JAN 2004)

FILE 'REGISTRY' ENTERED AT 09:43:03 ON 21 JAN 2004
L1 STRUCTURE UPLOADED
L2 QUE L1
L3 6 S L1 SSS SAM
L4 6 S L2 SSS SAM

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 09:44:16 ON 21 JAN 2004
L5 13 S L4
L6 6 DUPLICATE REMOVE L5 (7 DUPLICATES REMOVED)

FILE 'HOME' ENTERED AT 09:45:09 ON 21 JAN 2004

FILE 'REGISTRY' ENTERED AT 09:48:02 ON 21 JAN 2004
L7 SCREEN 2067
L8 STRUCTURE UPLOADED
L9 QUE L8 AND L7
L10 0 S L9 SSS SAM

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 09:48:42 ON 21 JAN 2004
L11 0 S L10

FILE 'HOME' ENTERED AT 09:48:58 ON 21 JAN 2004

FILE 'REGISTRY' ENTERED AT 09:49:27 ON 21 JAN 2004
L12 SCREEN 2067
L13 STRUCTURE UPLOADED
L14 QUE L13 AND L12
L15 0 S L14 SSS SAM

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 09:51:32 ON 21 JAN 2004
L16 0 S L15

FILE 'HOME' ENTERED AT 09:51:43 ON 21 JAN 2004

FILE 'REGISTRY' ENTERED AT 09:54:29 ON 21 JAN 2004
L17 SCREEN 2067
L18 STRUCTURE UPLOADED
L19 QUE L18 AND L17
L20 0 S L19 SSS SAM
L21 SCREEN 2067
L22 STRUCTURE UPLOADED
L23 QUE L22 AND L21
L24 2 S L23 SSS SAM
L25 SCREEN 2067
L26 STRUCTURE UPLOADED
L27 QUE L26 AND L25
L28 0 S L27 SSS SAM
L29 SCREEN 2067
L30 STRUCTURE UPLOADED
L31 QUE L30 AND L29
L32 1 S L31 SSS SAM

-> FIL HCAPLUS, CAPLUS, USPATFULL
COST IN U.S. DOLLARS

SINCE FILE ENTRY	TOTAL SESSION
3.36	42.40

FULL ESTIMATED COST

FILE 'HCAPLUS' ENTERED AT 09:59:08 ON 21 JAN 2004
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.

COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'CAPLUS' ENTERED AT 09:59:08 ON 21 JAN 2004
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.

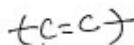
COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPATFULL' ENTERED AT 09:59:08 ON 21 JAN 2004
CA INDEXING COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

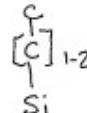
=> s 120
L33 0 L20

=> s 124
L34 11 L24

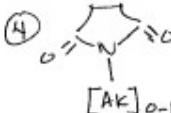
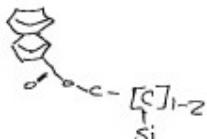
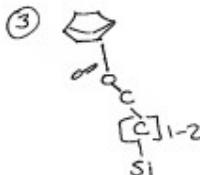
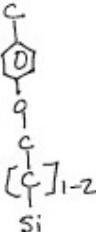
=> s 128
L35 0 L28



(1)



(2)



>> s 132
L36 2 L32

>> s 134 or 136
L37 13 L34 OR L36

>> duplicate remove 137
DUPLICATE PREFERENCE IS 'HCAPLUS, CAPLUS, USPATFULL'
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n
PROCESSING COMPLETED FOR L37
L38 7 DUPLICATE REMOVE L37 (6 DUPLICATES REMOVED)

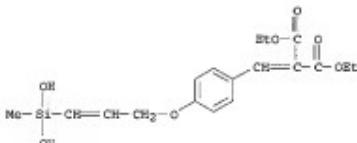
>> d 138 1-7 ibib hitatr

L38 ANSWER 1 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 1
ACCESSION NUMBER: 2003:216878 HCAPLUS
DOCUMENT NUMBER: 138-242881
TITLE: Skin cosmetic compositions containing active
ingredients and specified polysiloxanes
INVENTOR(S): Hayashi, Kyoko; Mitamara, Joji; Tokunaga, Yoshihiro
PATENT ASSIGNEE(S): Lion Corp., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 26 pp.
CODEN: JKXKAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003081806	A2	20030319	JP 2001-270198	20010906
PRIORITY APPLN. INFO.: JP 2001-270198 20010906				
IT 501947-86-0B	trimethyl-silyl-terminated			
RU	COS (Cosmetic use); BIGL (Biological study); USES (uses) (assumed monomer; skin cosmetic compns. contg. active ingredients and specified polysiloxanes)			
RM	501947-86-0 HCAPLUS			
CN	Propapenoic acid, [[4-[(3-(dihydroxymethylsilyl)-2- propenyl)oxy]phenyl)methylene]-, diethyl ester, homopolymer (9CI) (CA INDEX NAME)			

CM 1

CRM 200391-14-4
CMY C18 H24 O7 Si



L38 ANSWER 2 OF 7 USPATFULL on STN
ACCESSION NUMBER: 2003:13168 USPATFULL
TITLE: Positive working photoresist composition
INVENTOR(S): Mizutani, Kazuyoshi, Shizuoka, JAPAN
Sato, Kenichiro, Shizuoka, JAPAN
Kodama, Kunihiko, Shizuoka, JAPAN
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Kanagawa, JAPAN inc-U.S.
corporation

PATENT INFORMATION:	NUMBER	KIND	DATE
APPLICATION INFO.:	US 6506535	Bl	20030114
	US 2000-698221		20001030 (9)

PRIORITY INFORMATION:	NUMBER	DATE
	JP 1999-307317	19991028
	JP 1999-311785	19991122
	JP 1999-338487	19991129
	JP 1999-343714	19991202

DOCUMENT TYPE: Utility
FILE SEGMENT: GRANTED
PRIMARY EXAMINER: Baxter, Janet
ASSISTANT EXAMINER: Clarke, Yvette M.

LEGAL REPRESENTATIVE: Sughrue Mion, PLLC
NUMBER OF CLAIMS: 19
EXEMPLARY CLAIM: 1,3
NUMBER OF DRAWINGS: 0 Drawing Figure(s); 0 Drawing Page(s)
LINE COUNT: 2346
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT 337954-60-6P

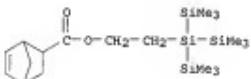
(acid-decomposable polymers for high-soln. pos. photoresists giving rectangular patterns)

RN 337954-60-6 USPATFULL

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-(2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl)ethyl ester, polymer with 2,5-furandione and methyl 2-propenoate (%CI) (CA INDEX NAME)

CN 1

CRN 337954-57-1
CNF C19 H40 O2 Si4



CN 2

CRN 108-31-6
CNF C4 H2 O3



CN 3

CRN 96-33-3
CNF C4 H6 O2



L38 ANSWER 3 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STM DUPLICATE 2
ACCESSION NUMBER: 2001726601 HCAPLUS
DOCUMENT NUMBER: 135:280511
TITLE: Positive-working photoresist compositions showing high resolution and high sensitivity and excellent storage stability
INVENTOR(S): Sato, Kenichiro
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 63 pp.
CODEN: JKXKAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

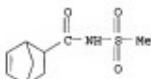
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001272784	A2	20011005	JP 2000-385724	200001219
PRIORITY APPLN. INFO.:			JP 1999-363302	A 19991221
			JP 2000-10773	A 20000119
			JP 2000-10774	A 20000119

OTHER SOURCE(S): MARPAT 135:280511
IT 363616-65-3P
RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(alk.-developing silyl-contg. polymer pos. photoresists having storage stability)
RN 363616-65-3 HCAPLUS
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethyl-3-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]propyl ester, polymer with 2,5-furandione and K-(methylsulfonyl)bicyclo[2.2.1]hept-5-ene-2-

carboxamide (9CI) (CA INDEX NAME)

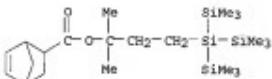
CM 1

CRN 363616-64-2
CNF C9 H13 N O3 S



CM 2

CRN 250589-01-6
CNF C22 H46 O2 Si4



CM 3

CRN 108-31-6
CNF C4 H2 O3



L38 ANSWER 4 OF 7 HCPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 3
ACCESSION NUMBER: 2001-423557 HCPLUS

DOCUMENT NUMBER: 135-38893

TITLE: Positive photoresist compositions for manufacture of semiconductor devices

INVENTOR(S): Sato, Kenichiro; Kodama, Munihiko; Mizutani, Kazuyoshi

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 66 pp.

CODEN: JKOKKAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 4

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001069812	A2	20010612	JP 1999-343714	19991202
US 6506535	NI	20030114	US 2000-698221	20001030
PRIORITY APPLN. INFO.:			JP 1999-307317	A 19991028
			JP 1999-331785	A 19991122
			JP 1999-336487	A 19991129
			JP 1999-343714	A 19991202

OTHER SOURCE(S): MARPAT 135:38893

IT 337954-60-6

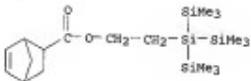
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(acid-decomposable polymers; improvement of exposure margin in pos. photoresists for manuf. of semiconductor devices)

RM 337954-60-6 HCPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]ethyl ester, polymer with 2,5-furandione and methyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 337954-57-1
CNF C19 H40 O2 Si4



CM 2

CRN 108-31-6
CWF C4 H2 O3



CM 3

CRN 96-33-3
CWF C4 H6 O2



138 ANSWER 5 OF 7 HCPLUS COPYRIGHT 2004 ACS on STX DUPLICATE 4
ACCESSION NUMBER: 2003-414682 HCPLUS

DOCUMENT NUMBER: 135:26888
TITLE: Alkali-developable positive-working photoresist

INVENTOR(S): Sato, Kenichiro; Mizutani, Kazuyoshi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, '71 pp.

CODEN: JKXKAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 4

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001154361	A2	20010608	JP 1999-338487	19991129
US 6506535	81	20030114	US 2000-698221	20001030
PRIORITY APPLN. INFO.:			JP 1999-307317	A 19991028
			JP 1999-331785	A 19991122
			JP 1999-338487	A 19991129
			JP 1999-343714	A 19991202

IT 337954-60-6P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material
use); PREP (Preparation); USES (Uses)

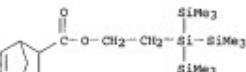
(polymer in alkali-developable pos.-working photoresist compn.)

RN 337954-60-6 HCPLUS

CM bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-(2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl)ethyl ester, polymer with 2,5-furan dicarboxylic acid and methyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 337954-57-1
CWF C19 H40 O2 Si4



CM 2

CRN 108-31-6
CWF C4 H2 O3



CM 3

CRN 96-33-3
CMF C4 H6 O2LJ8 ANSWER 6 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 5
ACCESSION NUMBER: 2001388948 HCAPLUS

DOCUMENT NUMBER: 135:12122

TITLE: Positive-working photoresist composition containing

sulfonium compound acid generator

INVENTOR(S): Sato, Kenichiro; Mizutani, Kazuyoshi

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 65 pp.

CODEN: JKXNAP

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 4

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 337954-60-6P	A2	20010529	JP 1999-331785	19991122
US 6506435	81	20030114	US 2000-698221	200001030
PRIORITY APPLN. INFO.:			JP 1999-307317	A 19991028
			JP 1999-331785	A 19991122
			JP 1999-338487	A 19991129
			JP 1999-343714	A 19991202

OTHER SOURCE(S): MARPAT 135:12122

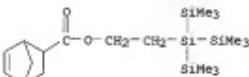
IT 337954-60-6P

RL: PMU (Preparation, unclassified); TEM (Technical or engineered material
use); PREP (Preparation); USNS (Uses);
(photoresist compn. contg. sulfonium compd. acid generator,
acid-decomposable polymer, basic compd. and surfactant)

RN 337954-60-6 HCAPLUS

CW Bicyclo[2.2.1]hept-5-enc-2-carboxylic acid, 2-[2,2,2-trimethyl-1,1-
bis(trimethylsilyl)disilanyl]ethyl ester, polymer with 2,5-furandione and
methyl 2-propenoate (SCI) (CA INDEX NAME)

CM 1

CRN 337954-57-1
CMF C19 H40 O2 Si4

CM 2

CRN 108-31-6
CMF C4 H2 O3

CM 3

CRN 96-33-3
CMF C4 H6 O2



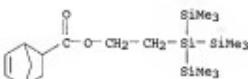
L38 ANSWER 7 OF 7 MCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 6
ACCESSION NUMBER: 2001336598 MCAPLUS
DOCUMENT NUMBER: 134146473
TITLE: High-resolution positive photoresist compositions
INVENTOR(S): Mizutani, Kazuyoshi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 60 pp.
CODEM: JKXXKAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 4
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001125212	A2	20010511	JP 1999-307317	19991028
US 6506535	B1	20030114	US 2000-698231	20001030
PRIORITY APPLN. INFO.:			JP 1999-307317	A 19991028
			JP 1999-331785	A 19991122
			JP 1999-338487	A 19991129
			JP 1999-343714	A 19991202

IT 337954-60-6P
RL INF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(acid-decomposable polymers for high-soln. pos. photoresists giving rectangular patterns)
RU 337954-60-6 MCAPLUS
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]ethyl ester, polymer with 2,5-furanedione and methyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 337954-57-1
CNF Cl9 H40 O2 Si4



CM 2

CRN 108-31-6
CNF C4 H2 O3



CM 3

CRN 96-33-3
CNF C4 H6 O2

